

The amination of silicon substrate — the first step of grafting of PAA/PAN brush onto silicon

Caixia Wan

National Synchrotron Radiation Lab (NSRL) & School of Nuclear Science and Technology
CAS Key Lab of Soft Matter Chemistry & Department of Polymer Science and Engineering
University of Science and Technology of China (USTC), Hefei, China

Introduction

Poly(acrylic acid) (PAA) brushes (either planar or spherical) have aroused great interest in the past decade due to its simple structure, abundant content of carboxyl groups and response to the environment stimulation. Because of its hydrophilicity, it is often used as copolymer to modify other hydrophobic polymer, such as polyacrylonitrile(PAN). In our experiments, we will graft the PAA/PAN brushes onto silicon substrate to characterize its configuration(mushroom or brush, figure 1) with neutron reflection (NR). But first, we should modify the silicon with silane coupling agent-APTES. We used the XPS spectra and contact angle to define the successful grafting of APTES onto silicon.

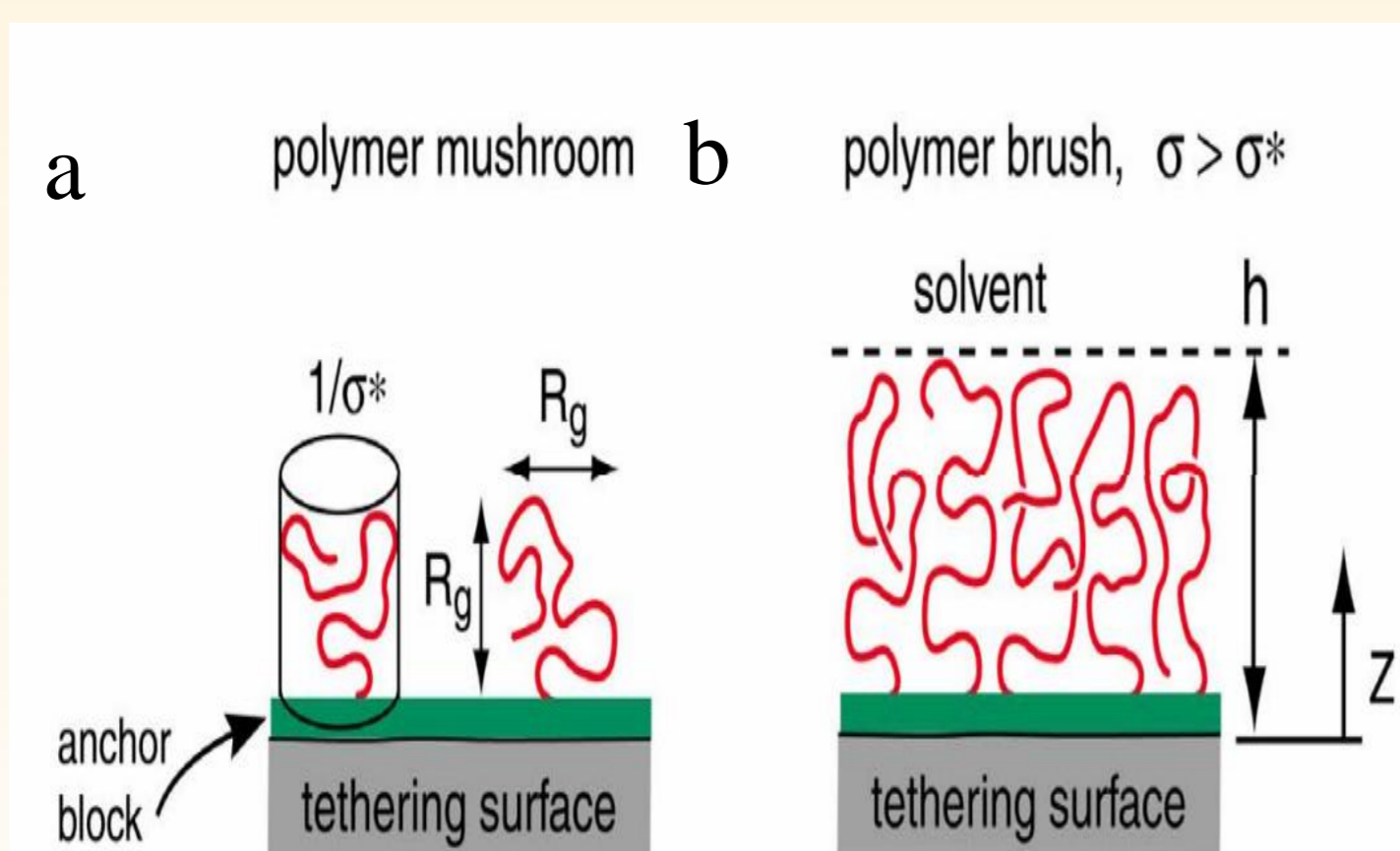


Fig.1 The two configuration of polymer brush on the substrate: a.mushroom;b.brush

Experiments and data

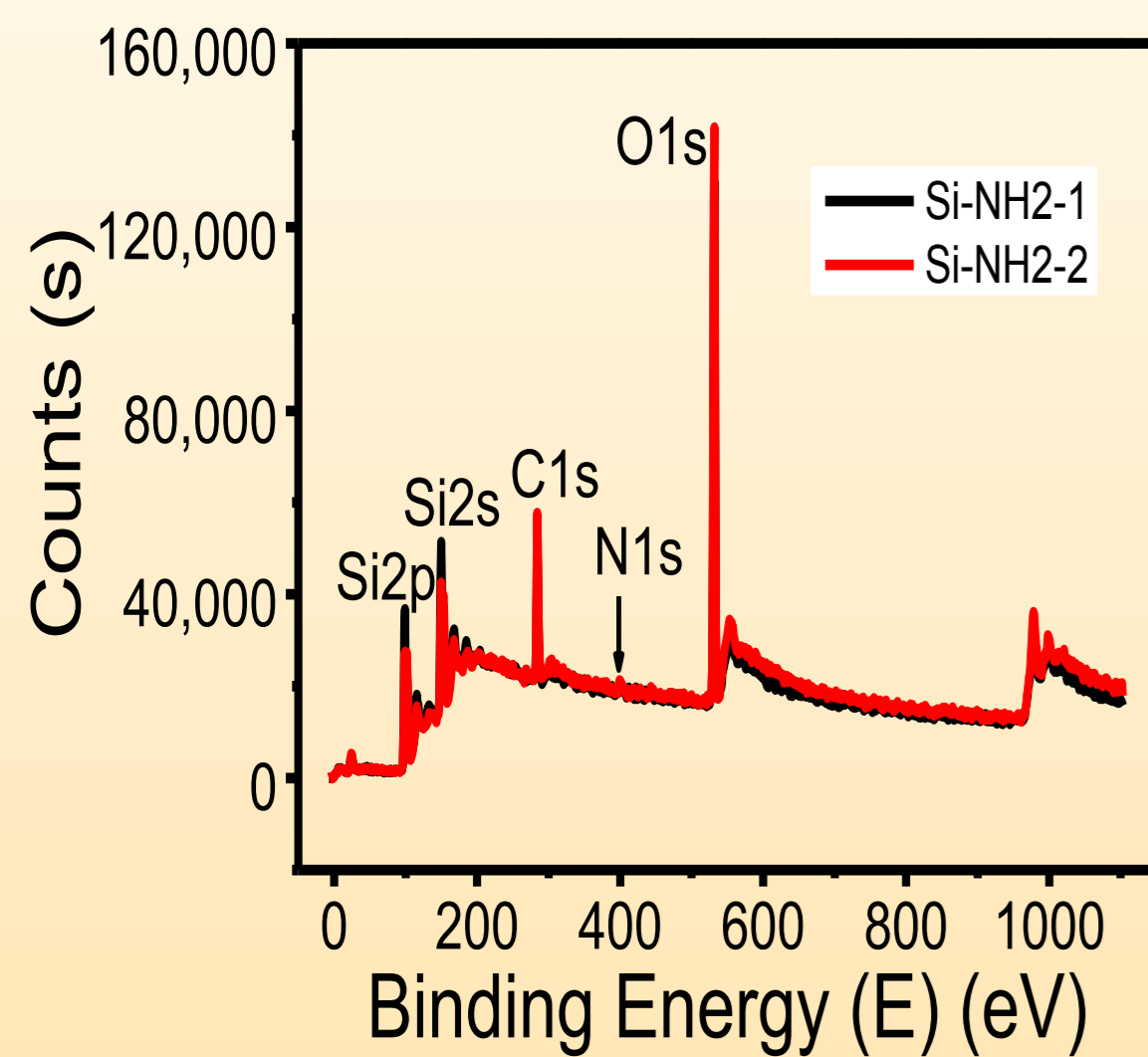


Fig.2 The XPS spectra of silicon modified by APTES

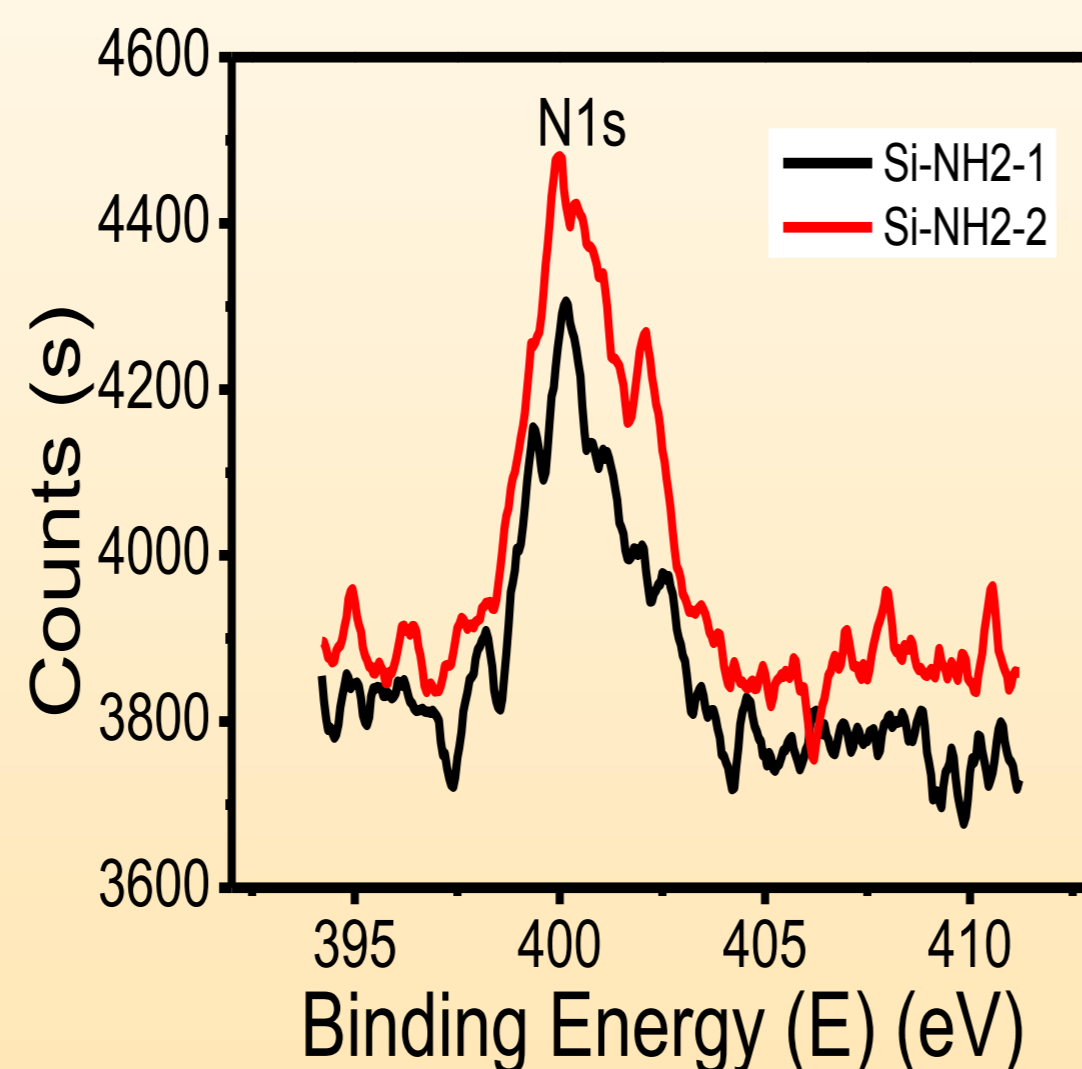


Fig.3 The XPS N1s spectra of silicon-NH2

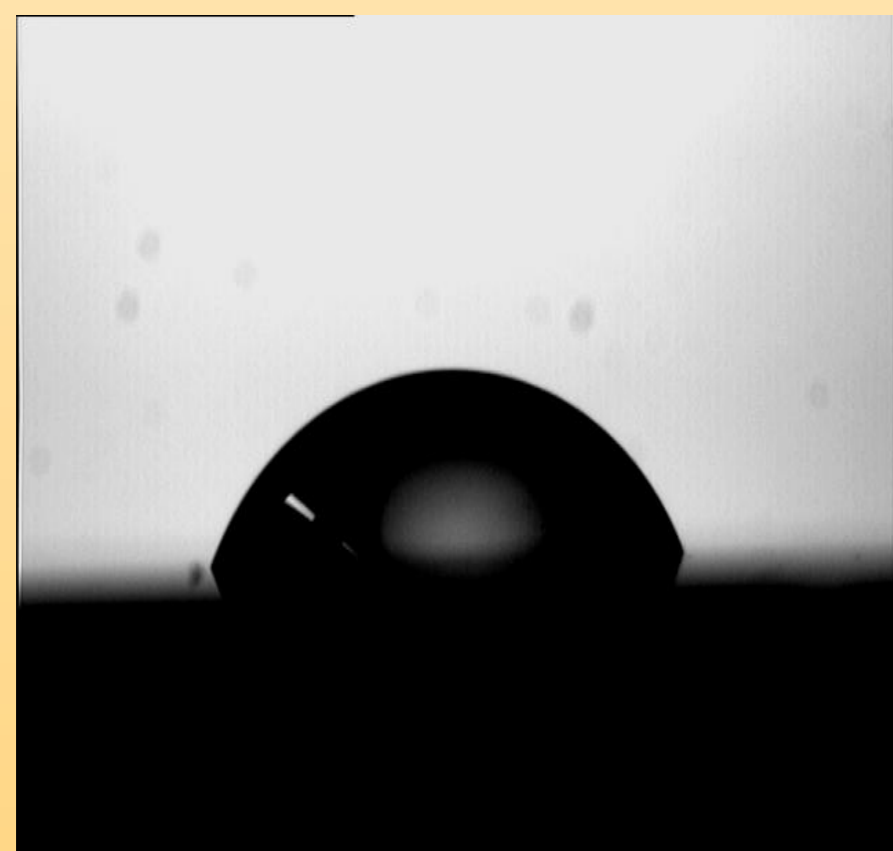


Fig.4 The contact angle of oxidized silicon substrate

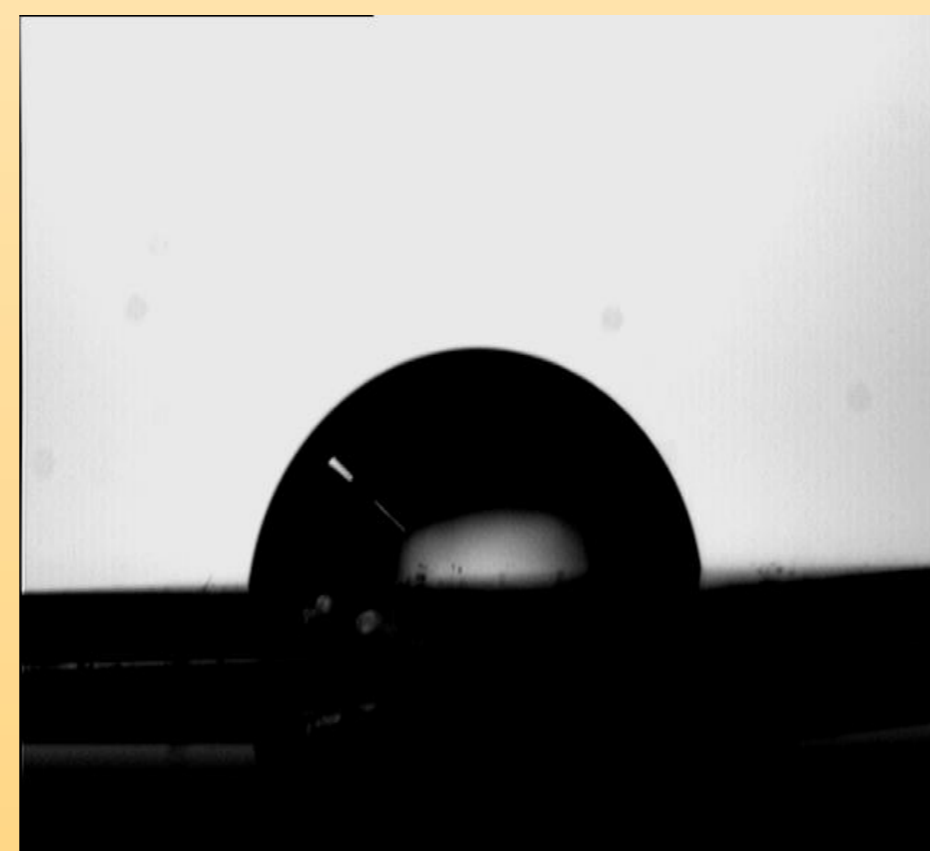


Fig.5 The contact angle of Silicon-NH2

Methods

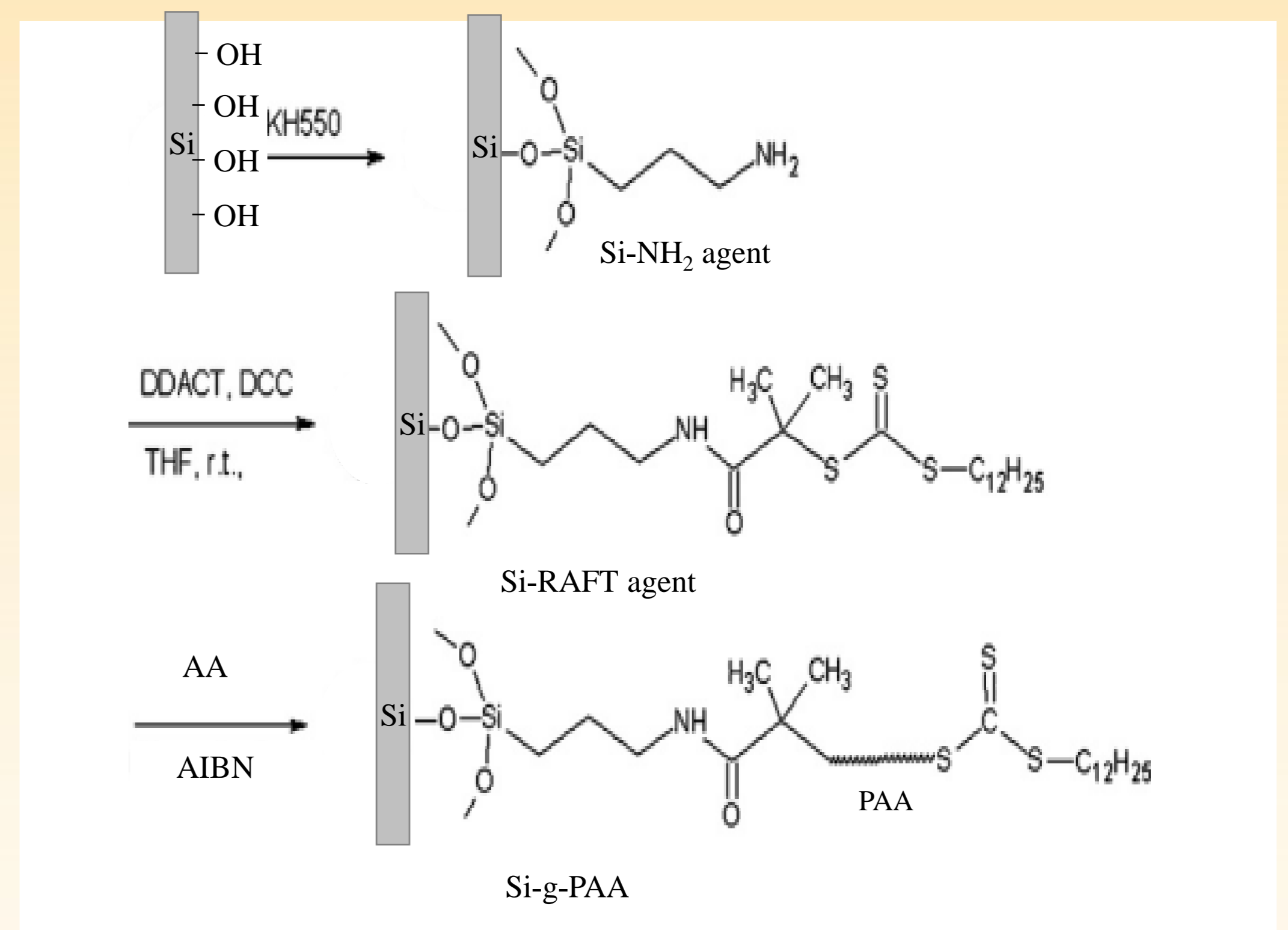


Fig.6 The diagrammatic sketch of the synthesis process of Si-PAA/PAN with RAFT methods.

Discussion and Conclusion

As the figure 6 shows, the synthesis of silicon-PAA/PAN has three processes:(1) the amination of silicon substrate, namely the modification of silicon with silane coupling agent KH550; (2) the amidation of NH2 with RAFT agent; (3) the RAFT grafting polymerization of PAA/PAN.

Up to now, we finished the first process. The results is shown in figure 2-5.

X-ray photon spectroscopy (XPS) is a precise and efficient means to analyze surface modifications. The successful modification of silicon substrate with APTES(KH550) agent was also confirmed by XPS analysis. It can be seen from figure 2 and figure 3 that the XPS spectra of silicon modified by APTES exhibited a signal of N1s suggested that APTES agent have been successfully.

The contact angle of silicon substrate before and after amination was characterized. As can be seen from figure 4 and figure 5, the contact angle of silicon was increased after amination. The reason is that before amination, the silicon has been oxidized by piranha solution ($H_2SO_4:H_2O_2=7:3$). There has been a layer of hydroxyl on the silicon, the hydrophilicity of which is larger than APTES.

In conclusion, the XPS spectra and the contact angle result suggested that the APTES has been grafted onto silicon substrate successfully.